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PATENT

Sheet 1 of 1

FORM PTO-1449 (Modified)
(Rev. 7-80)

U.S. Dept. of Commerce
Patent and Trademark Office

Atty Docket No.
SCP-6620 ()

Appln. No.
09/408,279

INFORMATION DISCLOSURE CITATION

Applicant(s)
JOHN J. ROSATO ET AL.

Filing Date
September 29, 1999

Group
1751

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

*Examiner Initials		Document Number	Date	Name	Class	Subclass	Filing Date
ME	AA	5,175,124	12/29/92	Winebarger	437	180	3/25/91
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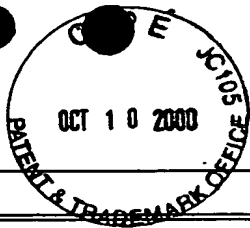
FOREIGN PATENT DOCUMENTS

*Examiner Initials		Document Number	Date	Country	Class	Subclass	Translation YES NO
ME	AC	EP0867924A2	9/30/96	Europe	H01L21	306	yes
	AD	EL0784336A2	7/16/97	Europe	H01L21	00	yes
	AE	EP0849772A1	6/24/98	Europe	H01L-21	00	yes
	AF	EP0596515B1	10/1/97	Europe	G03F7	42	yes
	AG	EP0817246A1	1/7/98	Europe	H01L21	00	yes
	AH	EP0874387A1	10/28/97	Europe	H01L21	00	yes
	AI	EP0649168A2	10/18/94	Europe	H01L21	306	yes
	AJ	EP0501492A2	2/27/92	Europe	H01L21	306	yes
	AK	EP0560324B1	8/19/98	Europe	C11D/	39	yes
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ME	AM	G. Schwartzkopf - Design of Low Alkalinity Organic Photoresist Strippers, Proceedings of the Symposia On Interconnects, Contact Metallization and Multilevel Metallization 1993.
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	AR	Stanley Wolf, Ph.D. - Silicon Processing for the VLSI Era - Volume 1, Process Technology, Chapter 15 Wet Processing: Cleaning, Etching and Liff-off - 1986

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Examiner <i>crf</i>	Date Considered <i>04/16/2001</i>
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				Filing Date September 29, 1999		Group 1751	
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	AB						
FOREIGN PATENT DOCUMENTS							
*Examiner Initials	AC	Document Number	Date	Country	Class	Subclass	Translation YES NO
MC		EP0846985A1	10/6/98	Europe	G03F	7/42	yes
OTHER DOCUMENTS							
AD							
Examiner 				Date Considered 04/16/01			
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